SP-011 Sputtering module for high sputtering rates

The SP-011 sputtering module for the use with CCU-010 HV or LV Compact Coating Units has a small form factor, yet offers all the features required for a broad range of PVD coating materials and for high sputtering rates. The module fully integrates a magnetron system, target, shutter, process pressure regulator and power electronics in a unique, robust unit that is guaranteed to be ready for operation and easy to maintain. An innovative interface with power and gas supply as well as signal transmission allows the modular system to be configured to work as a sputtering unit with just a single hand movement.

Basic containing:

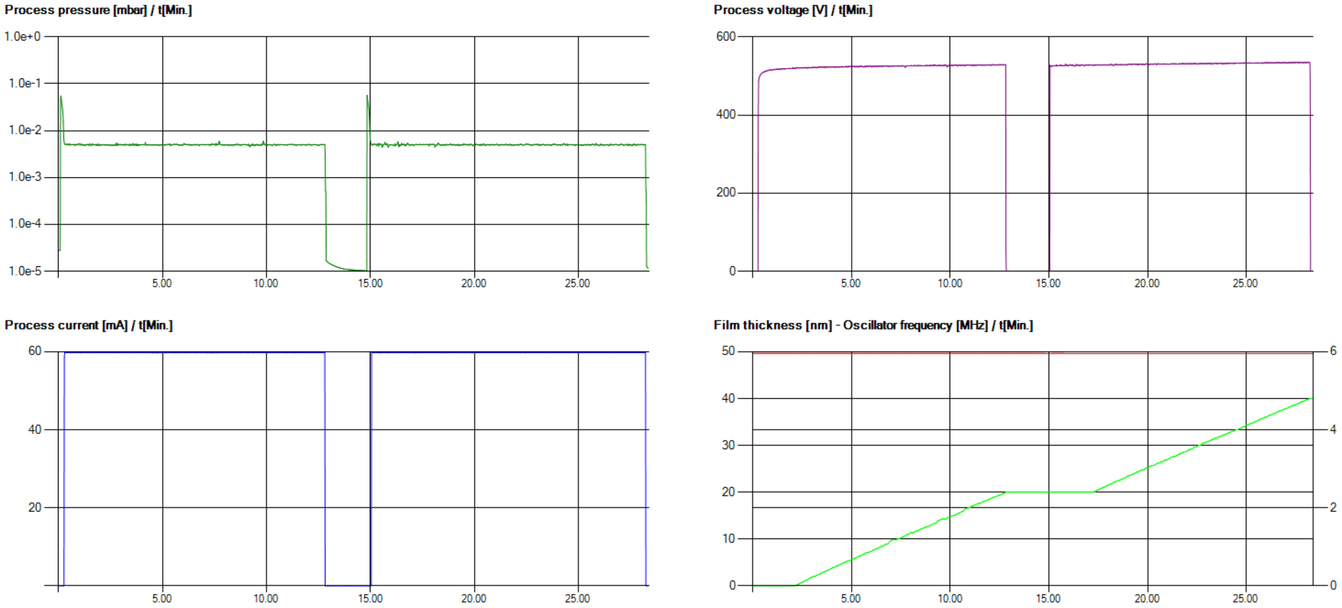
- Magnetron type B sputter head for high sputtering rates and wide range of target material
- For use with Ø 54mm targets up to 3mm thickness
- High voltage power supply
- Automatic target-shutter
- Target cooling system with temperature monitoring
- Electronic controlled process vacuum
- Implosion guard safety monitoring
- Process head interface (gas and electric)
- Tool for target exchange

Highlights

- Electronically controlled process vacuum ensures stable pressure in the process chamber.
- Circular gas orifice ensures homogeneous process gas distribution.
- Detection and monitoring of splinter protection guarantees safe operation.
- Target cooling with temperature monitoring ensures smooth operation.
- Uniform electrical and pneumatic interface for use with basic units CCU-010 HV or CCU-010 LV.
- Sputtering of indium tin oxide (ITO) ferromagnetic metals and Carbon possible.

SP-011 Characteristics

Carbon sputtering, two example runs with 20nm C coating each (CoatingLAB charts)



SP-011 compared to SP-010